#### **Gas Kinetics**

## Introduction

- Most deposition techniques rely on gas flow in a vacuum.
- We need a model for understanding;
  - the speed and energy of the gas molecules as a function of temperature and pressure,
  - how these molecules interact with each other and their surroundings,
  - and how mass, heat and momentum is transported by these molecules.

#### The Size of a Molecule (a very rough calculation)

- Take water (liquid  $H_2O$ ) as an example.
- Oxygen has 8 protons and 8 neutrons for a total of 16 <u>nucleons</u> and Hydrogen has 1 proton. So water has 16+1+1=18 nucleons

$$m_{P} \approx m_{N} \approx 1.66 \times 10^{-24} g$$

$$m_{H_{2}O} = 18m_{N} = 2.99 \times 10^{-23} g$$

$$N_{H_{2}O} = 1/m_{H_{2}O} = 3.35 \times 10^{22} \text{ molecules / } g$$

$$\rho_{H_{2}O} = 1.00g / cm^{3}$$

$$V_{H_{2}O} = \frac{1}{\rho_{H_{2}O}N_{H_{2}O}} = 2.99 \times 10^{-23} cm^{3} / \text{ molecule}$$

$$d_{H_{2}O} = 2 \times \sqrt[3]{\frac{3}{4}}V_{H_{2}O} = 5.64 \times 10^{-8} cm$$

ν4



### The Distance Between Molecules in a Gas

• Now take water vapor (gaseous  $H_2O$ ).

$$\rho_{H_2O} = 0.8 \times 10^{-3} \, g \,/\, cm^3$$
$$V_{H_2O} = \frac{1}{\rho_{H_2O} N_{H_2O}} = 3.73 \times 10^{-20} \, cm^3 \,/\, molecule$$

$$l_{H_2O} = \sqrt[3]{V_{H_2O}} = 3.34 \times 10^{-7} \, cm$$

 $l_{H_2O}\approx 6d_{H_2O}$ 



## Molecular Velocities

- Basic assumptions:
  - We'll assume an ideal gas where the gas molecules interact elastically (collisions are similar to the collisions of hard billiard balls).
  - The distance between molecules are large compared to their sizes.
  - There are no attractive or repulsive forces between the molecules and each molecule moves independently of the others.

## Maxwell-Boltzmann Distribution

• Under these assumptions, the molecules of a gas have velocities that are distributed according to:

$$f(v) = \frac{1}{n} \frac{dn}{dv} = 4\pi v^2 \sqrt{\frac{M}{2\pi RT}} \exp\left(-\frac{Mv^2}{2RT}\right)$$

where f is the fractional number of molecules, v is the velocity, M is the molecular weight, T is the temperature and R is the universal gas constant.



While the velocity of a single molecule depends on the temperature and its molecular weight, its kinetic energy is only dependent on temperature and is equally partitioned into the three coordinates.

### Pressure

- Since readily measurable quantities are temperature and pressure (and not number density or velocity) we need a more convenient relationship that relates them.
- Pressure arises from the momentum transfer from the gas molecules to the walls of the container.
- The average force on the walls of the container is given by:

$$\overline{F} = MN_m \frac{\overline{v_x}^2}{L} = \frac{1}{3}MN_m \frac{\overline{v}^2}{L} = \frac{MN_m}{3L} \frac{3RT}{M} = \frac{N_m RT}{L} = \frac{N_m RTA}{V}$$

$$P = \frac{\overline{F}}{A} = \frac{N_m RT}{V} \quad \text{then}$$

$$\overline{PV = N_m RT} \quad \text{or} \quad \overline{PV = Nk_B T} \quad \text{where } N_m \text{ is the gas and } N_m \text{ the gas and } N_m \text{ is the gas$$



where  $N_m$  is the total number of moles of the gas and N is the number of molecules

## Units of Pressure

- SI units: 1 Pascal (1 Pa) = 1 N/m<sup>2</sup>
   Not very practical
- 1 Torr = 133 Pa = 1 mm Hg
- 1 bar = 750 Torr =  $10^5$  Pa = 0.987 atm
- 1 atm = 760 Torr = 10100 Pa
- 1 psi = 51.71 Torr = 0.068 atm

## Mean Free Path

- In a vapor, gas molecules will be moving freely.
- Their motion is interrupted only by collisions with other molecules or the container.
- The average distance a molecule can move between collisions is called the mean free path.

## Rough Calculation of the MFP

• Suppose there is a gas molecule trying to get through an array of gas molecules.



Area blocked by one molecule



Probability that a collision will occur

$$R = \pi d^2 / l^2$$

Average number of layers between collisions

$$1/2R = l^2/2\pi d^2$$

$$MFP = \frac{l}{2R} = \frac{l^3}{2\pi d^2} = \frac{1}{2\pi n d^2}$$

where n is the number of gas molecules per cm<sup>3</sup>

### Rough Calculation of the MFP

In an ideal gas 
$$n = \frac{N}{V} = \frac{P}{k_B T}$$

$$MFP = \frac{1}{2\pi nd^2} = \frac{k_B T}{2\pi d^2 P}$$

More accurately

$$MFP = \frac{\sqrt{2}k_BT}{2\pi d^2P}$$

P (Torr)	MFP (cm)
760	10 <sup>-5</sup>
1	10 <sup>-2</sup>
0.001	10

# Molecular Flow Regimes

- Since film deposition depends on how a gas flows and the mean free path is a measure of the interaction between the gas molecules, it determines the type of gas flow that can happen.
- The flow of gas is characterized by the Knudsen number (Kn).

$$Kn = \frac{MFP}{L}$$

*L* is a dimension of the vacuum chamber

- If Kn < 0.01, many molecules in chamber, pressure is high, the flow is <u>viscous</u> (like a fluid).
- If Kn > 1, few molecules in chamber, pressure is low, gas flow is molecular and ballistic.
- If 1 > Kn > 0.01, the gas is in a transition regime where neither property is valid.

## Gas Transport: Diffusion

- Diffusion in gases is the mixing of one material (A) into another (B).
- Fick's Law for solids is still valid.

$$J = -D\frac{dn_A}{dx} \qquad D \propto \frac{T^{7/4}\sqrt{\frac{1}{M_A} + \frac{1}{M_B}}}{P(d_A + d_B)^2}$$

 In the ballistic regime (Kn > 1) diffusion will not occur (not enough molecules around).

## Gas Transport: Viscosity

• In a chamber, gas molecules traveling at different speed exert drag on each other.



where,  $\tau$  is the shear stress, *u* is the velocity in a direction perpendicular to *y* and  $\eta$  is the viscosity.



Again, in the ballistic regime, viscous interactions do not occur.

#### Gas Transport: Heat Conduction

- Heat can be transported through the transfer of kinetic energy between gas molecules.
- In the viscous regime, heat transfer between a heater and the substrate occurs through the collisions of the gas molecules in between.
- In the ballistic regime, the molecules don't collide with each other so heat transfer depends on the amount of flow of molecules (flux) from the heater to the substrate.

## Gas Flow

 Gas will flow when there is a pressure difference between different sections of a chamber.



### Conductance

- In a system with multiple components, the overall conductance is determined by how the components are hooked up.
- Series connections:

$$C_{sys} = \left(\frac{1}{C_1} + \frac{1}{C_2} + \frac{1}{C_3} + \dots\right)^{-1}$$

• Parallel connections:



$$C_{sys} = C_1 + C_2 + C_3 + \dots$$

# **Pumping Speed**

• The pumping speed  $S_p$ , is defined as the volume of gas passing the plane of the inlet port per unit time when the pressure at the pump inlet is  $P_p$ .

$$Q = P_p S_p$$



## Interaction With Surfaces

- Gas molecules colliding with the chamber walls result in pressure.
- Another possible interaction (and one crucial in film deposition) is gas impingement on other surfaces such as the substrate.
- A measure of the amount of gas incident on a surface is the flux.

## Flux

 The flux is the number of molecules that strike an element of a surface perpendicular to a coordinate direction, per unit time and area.

$$\Phi = \int_{0}^{\infty} v_{x} dn_{x} \longrightarrow \frac{\Phi}{N_{A}} = \frac{P}{\sqrt{2\pi MRT}}$$

$$\Phi = 3.513 \times 10^{22} \frac{P}{\sqrt{MT}}$$

with P expressed in Torrs

## **Deposition Rate**

• The flux of molecules on the surface leads to deposition where the rate of film growth depends on the flux.

$$\frac{dh_{film}}{dt} = \Phi\left(\frac{M_{film}}{\rho_{film}N_A}\right)$$

where  $M_{\rm film}$  is the molar molecular mass (g/mol) and  $\rho_{\rm film}$  is the film density (g/m<sup>3</sup>)

 Of course this assumes that there are no chemical reactions, bouncing off of molecules or diffusion into the surface.